Supplementary Information

Naphthyridinedione-based multifunctional small molecules for both photovoltaics and transistors application

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Scheme S1 Synthetic route of NTDC-N and NTDC-N-4F.



Fig. S1 (a) Molar extinction coefficients in 10 μ M CHCl₃ solution and (b) Absorption coefficient in thin film of NTDC-N and NTDC-N-4F.



Fig. S2 Cyclic voltammograms of NTDC-N, NTDC-N-4F, and ferrocene.



Fig. S3 2D GIWAXS patterns of (a) NTDC-N and (b) NTDC-N-4F neat films. The faint ring patterns around q = 1.5 Å⁻¹ and the bright ring patterns around q = 2 Å⁻¹ are originated from ITO substrates.



Fig. S4 Out-of-plane linecuts of GIWAXS patterns of pristine acceptor films, polymer:acceptor blend films, and polymer:acceptor blend films w/ CN. (a and c) NTDC-N and (b and d) NTDC-N-4F. Normalized peaks near π - π stacking pattern of films are described on (c) NTDC-N and (d) NTDC-N-4F.



Fig. S5 Device structure of OFET devices.



Fig. S6 Representative transfer (left side of (a and b), $V_{DS} = 100$ V) and output curves (right side of (a and b), $V_G = -100$ V) for top-contact bottom-gate *n*-channel mode OFETs with Al electrode of (a) NTDC-N and (b) NTDC-N-4F. Substrate temperature is 110°C. Channel width (*W*) and length (*L*) are 100 µm and 1 mm, respectively.



Fig. S7 Representative transfer (left, $V_{DS} = 100$ V for *n*-channel mode and $V_{DS} = -100$ V for *p*channel mode) and output curves (right, $V_G = -100$ V *n*-channel mode and $V_G = 100$ V for *p*channel mode) for top-contact bottom-gate OFETs with Al electrode of (a and c) NTDC-N and (b and d) NTDC-N-4F. *n*-Channel mode and *p*-channel mode OFET characteristics are on the top (a and b) and the bottom (c and d), respectively. Channel width (*W*) and length (*L*) are 100 µm and 1 mm, respectively.



Fig. S8 An image of NTDC-N and NTDC-N-4F.



Fig. S9 ¹H NMR and ¹³C NMR spectra of NTDC (CDCl₃).



Fig. S10 ¹H NMR and ¹³C NMR spectra of NTDC-CHO (CDCl₃).



Fig. S11 ¹H NMR and ¹³C NMR spectra of NTDC-N (CDCl₃).



Fig. S12 ¹H NMR and ¹³C NMR spectra of NTDC-N-4F (CDCl₃).

BHJ	Additive	V _{oc} [V]	J _{sc} [mA cm ⁻²]	FF	PCE [%]
PCE-10:NTDC-N	-	0.71	18.97	0.51	6.85
	DPE 0.5 vol%	0.71	13.97	0.57	5.70
	DIO 0.5 vol%	0.70	9.26	0.58	3.79
	CN 0.5 vol%	0.71	19.52	0.54	7.51
PCE-10:NTDC-N-4F	-	0.65	20.49	0.59	7.83
	DPE 0.5 vol%	0.63	19.87	0.61	7.61
	DIO 0.5 vol%	0.64	17.60	0.59	6.60
	CN 0.5 vol%	0.64	20.08	0.61	8.16

Table S1 Device performances of OPV devices using different additives.

Table S2 GIWAXS parameters of acceptors and blend films.	

Film	q _z (Å ⁻¹)	π-π stacking (Å)	FWHM (Å ⁻¹)	CCL (Å)
NTDC-N	1.6102	3.90	0.2840	22.12
PCE-10:NTDC-N	1.6406	3.83	0.1876	33.49
PCE-10:NTDC-N w/ CN	1.6048	3.91	0.2209	28.44
NTDC-N-4F	1.6485	3.81	0.2702	23.25
PCE-10:NTDC-N-4F	1.6349	3.84	0.2021	31.09
PCE-10:NTDC-N-4F w/ CN	1.6349	3.84	0.2082	30.18

Material	Substrate temperature	μ _{e.avg} ^{a)} [cm ² V ⁻¹ s ⁻¹]	μ _{e.max} ^{b)} [cm ² V ⁻¹ s ⁻¹]
NTDC-N	25℃	(1.67 ± 0.25) × 10 ⁻³	2.32 × 10 ⁻³
	70℃	$(2.34 \pm 0.51) \times 10^{-3}$	3.14×10^{-3}
	110°C	$(1.05 \pm 0.17) \times 10^{-2}$	1.31 × 10 ⁻²
NTDC-N-4F	25℃	$(1.20 \pm 0.09) \times 10^{-3}$	1.31 × 10 ⁻³
	70℃	$(1.79 \pm 0.17) \times 10^{-3}$	2.19 × 10 ⁻³
	110°C	$(3.48 \pm 0.35) \times 10^{-3}$	4.21 × 10 ⁻³
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 Table S3 Summary of OFET device performances according to substrate temperatures.

^{*a*)} Average electron mobility. ^{*b*)} Maximum electron mobility.